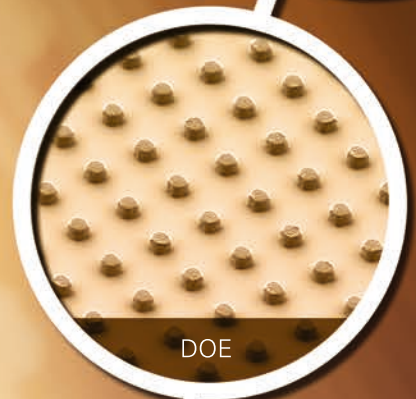


MLA150

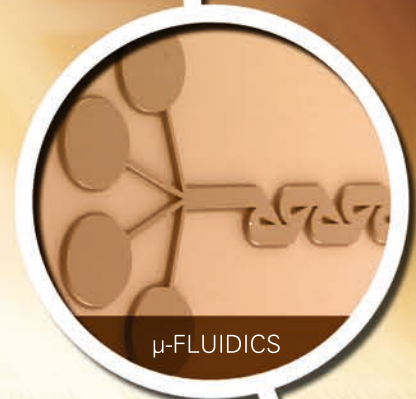
HEIDELBERG INSTRUMENTS



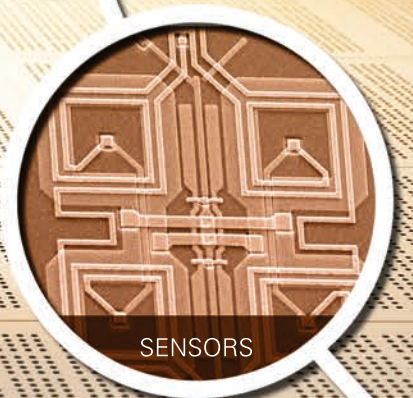
MEMS



DOE



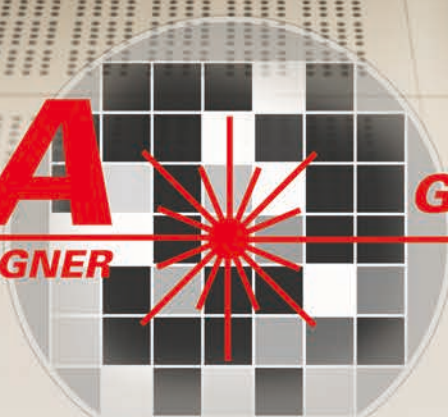
μ-FLUIDICS



SENSORS

MLA

MASKLESS ALIGNER



GO MASKLESS
ACHIEVE MORE



Hrs. Min.
00:03

STEP 1: SYSTEM SETUP

- Intuitive User Interface
- Multi-user capabilities
- Support for all standard input formats (dxf, gdsii, cif, gerber)
- CAD Software for design creation included
- Resist database

MLA 150



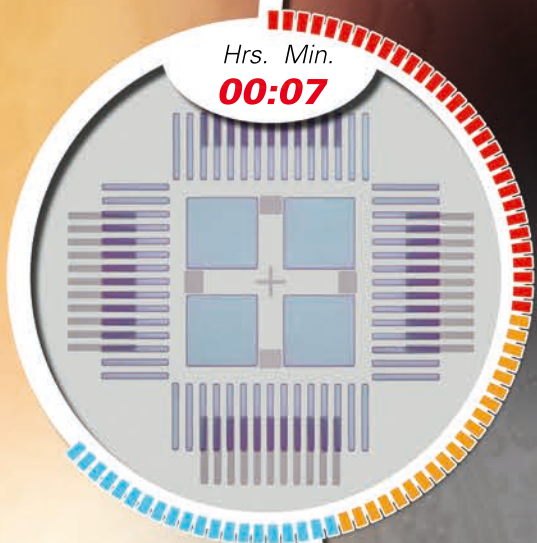
MORE INFO? SCAN THIS!



Hrs. Min.
00:05

STEP 2: LOADING

- Simple loading procedure
- One chuck for all substrates from 5 x 5 mm² to 150 x 150 mm²
- Automatic substrate size detection
- No need for edge-bead removal or wedge compensation



Hrs. Min.
00:07

STEP 3: ALIGNMENT

- High precision topside and backside alignment
- Fast alignment procedure
- Distortion compensation
- Simple alignment on thick resists and small substrates
- Alignment accuracy ≤ 500 nm

MLA
MASKLESS ALIGNER



Hrs. Min.
00:11

STEP 4: EXPOSURE

- Min. feature size of 1 μ m
- Exposure time for 50 x 50 mm² approx. 4 min.
- Non-contact exposure
- High Aspect Ratio exposures in thick resist
- Automatic labeling and serialization
- Compatible to g-, h- and i-line resists



GO MASKLESS —————
ACHIEVE MORE

Specifications depend on individual process conditions and can vary according to equipment configurations. Design and specifications are subject to change without prior notice.

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